

# Room-temperature persistent spectral hole burning of $\text{Eu}^{3+}$ coupling with $\text{Al}^{3+}$ in glass

Masayuki Nogami\* and Tomotaka Ishikawa

*Department of Materials Science and Technology, Nagoya Institute of Technology, Showa Nagoya 466-8555, Japan*

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Room-temperature persistent spectral hole burning was observed in  $\text{Eu}^{3+}$ -doped  $\text{Al}_2\text{O}_3\text{-SiO}_2$  glasses. The sol-gel-derived  $\text{Eu}^{3+}$ -doped glasses were heated in hydrogen gas and irradiated with x ray, in which the oxygen deficient centers were induced in Al-O bonds and some  $\text{Eu}^{3+}$  ions were reduced into  $\text{Eu}^{2+}$  by heating in hydrogen gas. The spectral holes were burned in the excitation spectra of the  ${}^7F_0 \rightarrow {}^5D_0$  transition of  $\text{Eu}^{3+}$ . The maximum depth of the hole burned at room temperature was found to be  $\sim 10\%$  of the total excitation intensity for both the glasses and independent of the treatment conditions of glasses. A proposed model for hole burning is the excitation of the  $\text{Eu}^{3+}$  ion and subsequent hole trapping in the oxygen-defect centers in the Al-O bonds. The burnt holes were easily erased by laser irradiation with the energy different from burning one.

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## I. INTRODUCTION

Persistent spectral hole burning (PSHB) phenomenon has attracted much attention because of its potential use in high-density frequency-selective optical memories.<sup>1,2</sup> The primary object of this strategy involves the fabrication of stable materials exhibiting highly efficient hole burning at room temperature. Many materials doped with organic dye molecules and rare-earth ions display the PSHB property, however, in most of them, PSHB cannot be observed near room temperature.  $\text{Sm}^{2+}$  and  $\text{Eu}^{3+}$  ions are special cases, where the PSHB can be observed at room temperature.<sup>3-13</sup> Room temperature PSHB materials with high efficiency, if easily prepared, have a high potential for use in high-density memory devices. As a host material for these rare earth ions, glass is more favorable than crystals because of its wide distribution of the rare-earth ions and high transparency.<sup>9-13</sup> When the glass is melted, the  $\text{Sm}^{3+}$  ions are incorporated as the trivalent state. To reduce the  $\text{Sm}^{3+}$  ions, it is necessary to melt the glass at high temperature under a strong reducing atmosphere.<sup>9-11</sup> Recently, we succeeded in preparing the  $\text{Sm}^{2+}$  and  $\text{Eu}^{3+}$  ions-doped glasses by a sol-gel method and observed room temperature PSHB.<sup>14-17</sup> The sol-gel process is appropriate for preparing a glass at moderately lower temperatures than required for the conventional melting method.

$\text{Sm}^{2+}$  and  $\text{Eu}^{3+}$  ions have the same  $4f^6$  electron configuration the lowest and first excited states of which are  ${}^7F_0$  and  ${}^5D_0$ , respectively. The hole spectra are observed on the excitation spectra of the  ${}^7F_0 \rightarrow {}^5D_0$  transition of the  $\text{Sm}^{2+}$  and  $\text{Eu}^{3+}$  ions, though the hole burning mechanism is still unknown. A possible mechanism for the hole burning of these ions is the photoinduced charge transfer between the rare earth ions by the laser irradiation. The photoionization of the  $\text{Sm}^{2+}$  ions into  $\text{Sm}^{3+}$  has been observed in the  $\text{Sm}^{2+}$ -doped  $\text{BaClF}$  crystals.<sup>3,6,8</sup> The released electrons are captured by  $\text{Sm}^{3+}$  ions to form the  $\text{Sm}^{2+}$ . On the other hand, Fujita *et al.* considered that in the  $\text{Eu}^{3+}$ -doped glasses, the hole is burned by the reduction of the  $\text{Eu}^{3+}$  ions and the released holes are captured by the  $\text{Eu}^{2+}$ .<sup>12,13</sup>

In contrast, we found that the  $\text{Eu}^{2+}$  ions do not necessarily act as the main trap for holes. In the sol-gel derived glasses,

the room temperature PSHB of the  $\text{Eu}^{3+}$  ions is observed only in the  $\text{Al}^{3+}$  ion-containing silicate glasses, and not in the  $\text{SiO}_2$  glass.<sup>17</sup> We postulated that the electron transfer takes place between the  $\text{Eu}^{3+}$  ions and the matrix structure. Further investigations are necessary to clarify the PSHB mechanism of the  $\text{Eu}^{3+}$  ions doped in glasses.

The aim of this work is to study how the glass structure relates to the room-temperature PSHB of the  $\text{Eu}^{3+}$  ions doped in  $\text{Al}_2\text{O}_3\text{-SiO}_2$  glasses. Some of the glasses were heated in a hydrogen gas atmosphere, while others were irradiated using an x ray. The effect of the  $\text{Eu}^{2+}$  ions and the defect structure in the Al-O polyhedra is discussed in relation to the hole-burning efficiency. This report is very significant when considering the hole-burning mechanism and the application of PSHB glasses to memory devices.

## II. EXPERIMENT

$1\text{Al}_2\text{O}_3 \cdot 9\text{SiO}_2$  (mole ratio) glasses containing nominally 10 wt. %  $\text{Eu}_2\text{O}_3$  were prepared by the sol-gel method using commercially available  $\text{Si}(\text{OC}_2\text{H}_5)_4$ ,  $\text{Al}(\text{OC}_4\text{H}_9^{\text{sec}})_3$ , and  $\text{EuCl}_3 \cdot 6\text{H}_2\text{O}$ . A detailed explanation of the gel preparation is given elsewhere.<sup>16,17</sup> The gels were heated in air at  $500^\circ\text{C}$  for 2 h. The  $\sim 1$  mm thick glasses were polished with fine  $\text{CeO}_2$  powders, followed by heating in air at  $800^\circ\text{C}$  for 2 h. The obtained glasses showed optical properties characteristic of the  $\text{Eu}^{3+}$  ions, i.e., absorption bands at 465 and 395 nm and fluorescence bands around 580, 590, 615, and 645 nm in the visible region, all of which are assigned to the  $f$ - $f$  transitions of the  $\text{Eu}^{3+}$  ions.

As previously reported, when the glasses are heated in air, a large amount of hydroxyl bonds remain in the glass and the spectral holes are burned by the rearrangement of the hydroxyl bonds surrounding the  $\text{Eu}^{3+}$  ions.<sup>15,16</sup> To eliminate the effect of the hydroxyl bonds on the hole burning, the glasses were heated in a vacuum at  $800^\circ\text{C}$  for 2 h, followed by heating under a flowing mixed gas with 20%  $\text{H}_2$ –80%  $\text{N}_2$  at 500 to  $800^\circ\text{C}$ . The x-ray irradiation was performed using the  $\text{CuK}\alpha$  line with 40 kV and 20 mA at room temperature for 1, 7, and 14 h. The PSHB was observed on the excitation spectra of the  ${}^7F_0 \rightarrow {}^5D_0$  transition of  $\text{Eu}^{3+}$  by scanning a

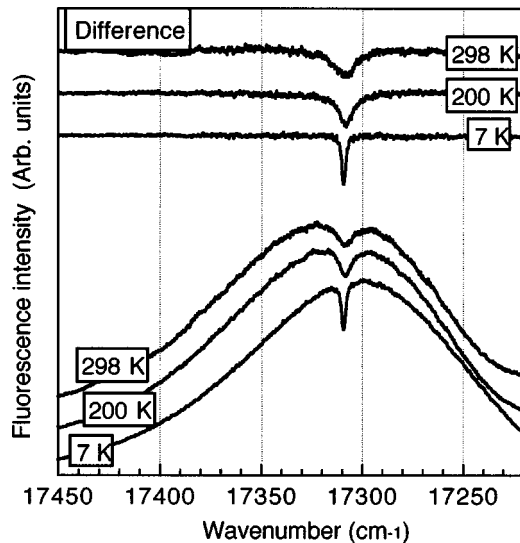


FIG. 1. PSHB spectra, burned and measured at 7, 200, and 298 K, of  $\text{Eu}^{3+}$ -doped  $1\text{Al}_2\text{O}_3 \cdot 9\text{SiO}_2$  glass heated in  $\text{H}_2$  gas at  $600^\circ\text{C}$  for 1 h. At the top is shown the difference between the fluorescence intensities before and after burning.

Rhodamine 6G dye laser over the  ${}^7F_0 \rightarrow {}^5D_0$  transition while monitoring the fluorescence of the  ${}^5D_0 \rightarrow {}^7F_2$  transition at 619 nm.

### III. RESULTS AND DISCUSSION

#### A. Room temperature hole burning for glass heated in $\text{H}_2$ gas

The sol-gel-derived glasses typically contain a large amount of hydroxyl bonds in glass, because water is used in the hydrolysis reaction of raw materials. We already reported that the PSHB is observed in these sol-gel-derived  $\text{Eu}^{3+}$ -doped glasses and the hole depth increases proportionally with the increasing OH content.<sup>15,16</sup> On the other hand, the present glasses were heated in a vacuum prior to the heat treatment in  $\text{H}_2$  gas, resulting in a lower OH content. We confirmed that no PSHB is observed in these glasses at any temperature prior to heat treatment.

When the glasses are heated in  $\text{H}_2$  gas, they become faintly yellow. The hole was burned by irradiating with a laser with a power of  $\sim 300$  mW at a  $\sim 2$  mm diameter spot at the wavelength around the peak position of the  ${}^7F_0 \rightarrow {}^5D_0$  transition of the  $\text{Eu}^{3+}$  ions for 30 min. Typical hole spectra, burned and measured at 7, 200, and 298 K, are shown in Fig. 1. The holes are clearly observed at the burning position of  $17310\text{ cm}^{-1}$ . The hole width (FWHM) is 1.9, 8.1, and  $12.6\text{ cm}^{-1}$  at 7, 200, and 298 K, respectively. The hole depth, defined as the depth to the total fluorescence intensity at the burning wave number, is 21, 17, and 13%, respectively. This room-temperature PSHB discovery for the  $\text{Eu}^{3+}$  ions is of significant importance in basic and practical investigations of the PSHB materials.

Figure 2 shows the optical absorption and fluorescence spectra of the glass before and after heating in  $\text{H}_2$  gas at  $600^\circ\text{C}$  for 1 h. The glass heated in air has optical properties characteristic of the  $\text{Eu}^{3+}$  ions, i.e., small and sharp absorp-

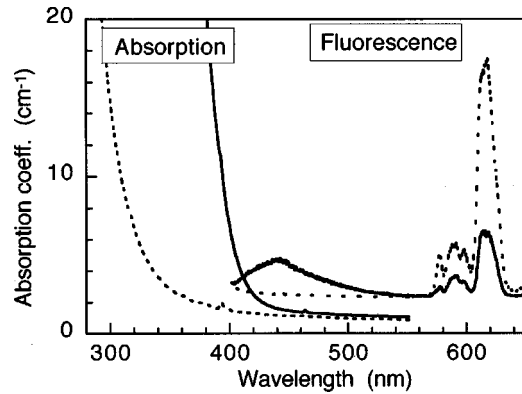


FIG. 2. Optical absorption and fluorescence spectra of  $\text{Eu}^{3+}$ -doped  $1\text{Al}_2\text{O}_3 \cdot 9\text{SiO}_2$  glass before (dotted lines) and after (solid lines) heating in  $\text{H}_2$  gas at  $600^\circ\text{C}$  for 1 h. The fluorescence was obtained using a xenon 395-nm excitation wavelength.

tion bands peaking at 394 and 465 nm in the absorption spectrum and fluorescence bands ranging from 570 to 660 nm in the visible wavelength region, all of which are assigned to the  $f-f$  transitions of the  $\text{Eu}^{3+}$  ions. On the other hand, the absorption spectrum of glass after heating in  $\text{H}_2$  gas shows the increase in absorption below 400 nm in addition to the sharp lines of the  $\text{Eu}^{3+}$  ions. The absorbance in the violet wavelength region suggests the existence of the  $\text{Eu}^{2+}$  ions.<sup>18</sup> The  $\text{Eu}^{2+}$  ion has a  $4f^7$  configuration, the excited  ${}^6P$  levels of which may lie close to the first excited level of the  $4f^65d$  configuration and the optical spectra due to the  $f-d$  transitions are usually broadened and dependent on the surroundings of the  $\text{Eu}^{2+}$  ions. However, the observed absorption band could not be resolved into its components due to the limited resolution of the spectroscopy used. On the other hand, the broad and asymmetric fluorescence band peaking at a 440-nm wavelength is observed in the  $\text{H}_2$  gas-treated glass. The broad fluorescence around 440 nm can be assigned to the  $4f^65d \rightarrow f^7({}^8S_{7/2})$  transition of the  $\text{Eu}^{2+}$  ions.<sup>19</sup> The relaxation pathway of the excited electrons is associated with the nonradiative relaxation of the electrons to the lowest energy level of the  $4f^65d$  configuration and the radiative transition into the ground  ${}^8S_{7/2}$  level.

It was found that the fluorescence intensity of the 440-nm band increases with increased heating time, whereas the intensity of the  $\text{Eu}^{3+}$  ions decreased. Contrary to the absorption intensity, which is linearly related to the concentration of the rare earth ions, the fluorescence intensity is not initially determined by the concentration of the rare-earth ions. Therefore, the ratio of the fluorescence intensity of  $\text{Eu}^{2+}$  and  $\text{Eu}^{3+}$  can be determined. Shown in Fig. 3 is the ratio of the intensity of the bands at 440 nm ( $4f^65d \rightarrow {}^8S_{7/2}$  transition of  $\text{Eu}^{2+}$ ) and 619 nm ( ${}^5D_0 \rightarrow {}^7F_2$  transition of  $\text{Eu}^{3+}$ ) as a function of the heating time. It is evident that the ratio of  $\text{Eu}^{2+}/\text{Eu}^{3+}$  increases as the heating time increases. We should point out that the  $\text{Eu}^{3+}$  ions are completely changed

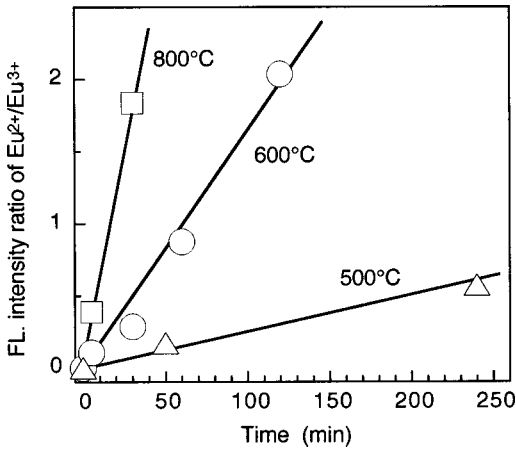


FIG. 3. Fluorescence intensity ratio of  $4f^65d \rightarrow {}^8S_{7/2}$  ( $\text{Eu}^{2+}$ ) to  ${}^5D_0 \rightarrow {}^7F_2$  ( $\text{Eu}^{3+}$ ) transition for  $\text{Eu}^{3+}$ -doped  $1\text{Al}_2\text{O}_3 \cdot 9\text{SiO}_2$  glass as a function of the heat treatment time in  $\text{H}_2$  gas at 500, 600, and 800 °C. The fluorescence intensities for the  $\text{Eu}^{3+}$  and  $\text{Eu}^{2+}$  ions were measured at 619 and 440 nm, respectively.

into the  $\text{Eu}^{2+}$  ions after heating for a long time. The total time required is shorter for the glass heated at high temperature.

The efficiency of the hole burning was measured for the glasses heated at 500 to 800 °C in  $\text{H}_2$  gas. The holes were burned by laser irradiation at a power of 300 mW for 30 min at 200 K. The hole depth, defined as the ratio of the depth to the total fluorescence intensity at the burning wave number, is plotted in Fig. 4 as a function of the heating time and temperature. The hole depth increases as the heat-treatment time increases and approaches a maximum depth of about 18%. It is evident, however, that a prolonged heat-treatment results in a decreased hole depth.

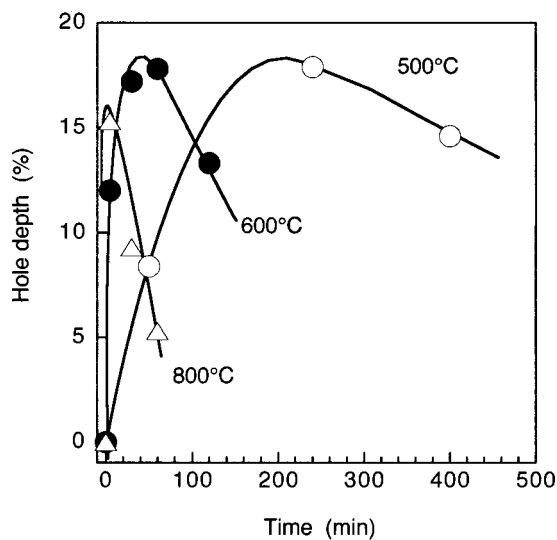


FIG. 4. Hole depth as a function of  $\text{H}_2$  gas heat-treatment time and temperature of  $\text{Eu}^{3+}$ -doped  $1\text{Al}_2\text{O}_3 \cdot 9\text{SiO}_2$  glass. Holes were burned at 200 K and hole depth was defined as the depth to total fluorescence intensity.

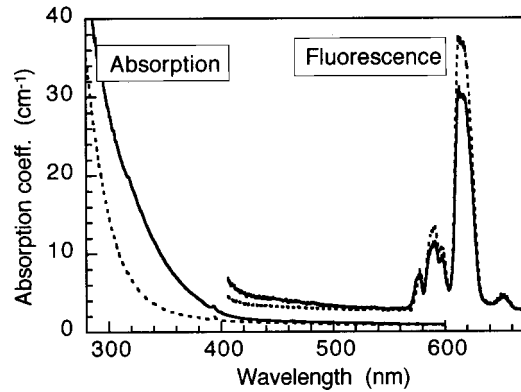


FIG. 5. Optical absorption and fluorescence spectra of  $\text{Eu}^{3+}$ -doped  $1\text{Al}_2\text{O}_3 \cdot 9\text{SiO}_2$  glass before (dotted lines) and after (solid lines) x-ray irradiation for 14 h at room temperature. The fluorescence was obtained using a xenon 395-nm excitation wavelength.

### B. Room temperature hole burning for glass irradiated by x ray

The glasses were irradiated by  $\text{Cu-K}\alpha$  x ray, the optical absorption and fluorescence spectra of which are shown in Fig. 5. There is no change in the fluorescence spectra before and after the x-ray irradiation except for a slight decrease in the intensities of the  $\text{Eu}^{3+}$  ions. No fluorescence band of the  $\text{Eu}^{2+}$  ions is observed at around 440 nm. However, the x-ray-irradiated glass shows an induced-absorbance in the ultraviolet wavelength range below 400 nm. This absorbance should be assigned to optical sites other than the  $\text{Eu}^{2+}$  ions.

The hole was burned on the  ${}^7F_0 \rightarrow {}^5D_0$  transition of the  $\text{Eu}^{3+}$  ions. The PSHB spectra, burned and measured at 7, 200, and 298 K, are shown in Fig. 6. The width (FWHM) and depth (defined as the depth to the total fluorescence in-

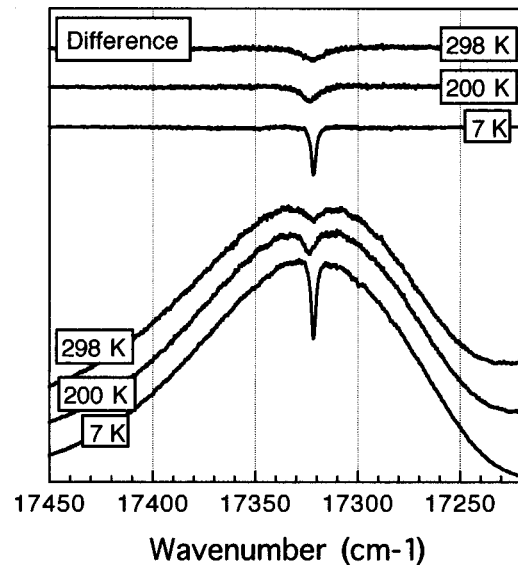


FIG. 6. PSHB spectra, burned and measured at 7, 200, and 298 K, of  $\text{Eu}^{3+}$ -doped  $1\text{Al}_2\text{O}_3 \cdot 9\text{SiO}_2$  glass irradiated with x ray for 14 h at room temperature. At the top is shown the difference between the fluorescence intensities before and after burning.

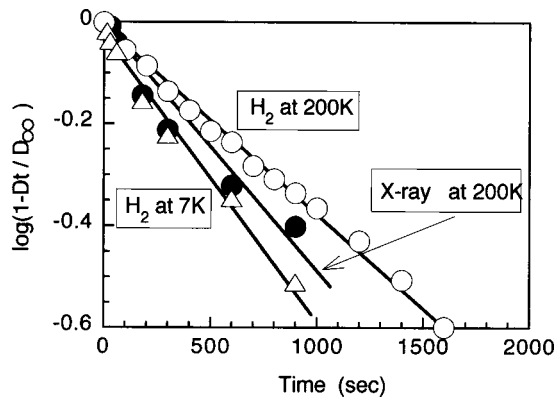


FIG. 7. Logarithmic plots of the dependence of hole depth on the burning time for  $\text{Eu}^{3+}$ -doped  $1\text{Al}_2\text{O}_3 \cdot 9\text{SiO}_2$  glass heated in  $\text{H}_2$  gas or irradiated with x ray. Holes were burned at 7 and 200 K.

density) of the holes burned at 7, 200, and 298 K are 2.5, 8.1, and  $12.5 \text{ cm}^{-1}$ , and 40, 12, and 9 %, respectively. This behavior is comparable to those of the holes burned in the glasses heated in  $\text{H}_2$  gas. It was also found that the hole depth increased with the increased x-ray-irradiation time. Compared to the  $\text{H}_2$  gas-heated glasses, the x-ray-irradiated glasses show strong fluorescence intensities from the  $\text{Eu}^{3+}$  ions. This greatly simplifies the observation of the hole spectra, which is a valuable quality for PSHB materials.

The dependence of the hole-burning efficiency on the burning time was studied for the  $\text{H}_2$ -gas-treated and the x-ray-irradiated glasses. We found that the hole depth increases with burning time and approaches a saturated level. If the hole is formed by the charge transfer between the burnt and unburnt states of the  $\text{Eu}^{3+}$  ions, the conversion rate of the  $\text{Eu}^{3+}$  ions is determined by the first-order kinetics. Assuming that the hole depth corresponds to the concentration of the burned  $\text{Eu}^{3+}$  ions, the hole depth  $D_t$  can be written as<sup>20,21</sup>

$$D_t = D_\infty [1 - \exp(-Kt)], \quad (1)$$

where  $D_\infty$  is the hole depth after an infinite period and  $K$  is a rate constant. The hole-growth data are plotted according to Eq. (1) in Fig. 7, where the  $D_\infty$  value was determined by the least-squares fit of the equation. The data follow Eq. (1), indicating that the hole burning is controlled by the rate equation and the rate constant increased with the decreased burning temperature. These seems to be no difference in the samples between these heated in  $\text{H}_2$  gas and irradiated by x ray. These results strongly suggest that the PSHB is formed by the same process in the  $\text{H}_2$ -gas heated and the x-ray-irradiated glasses.

### C. Effect of the glass composition on the hole burning

The observation of the room temperature PSHB is a special case. In a previous paper, we reported that the  $\text{SiO}_2$  glass does not demonstrate PSHB at room temperature, even though heating in  $\text{H}_2$  gas.<sup>17</sup> The  $\text{SiO}_2$  glass was prepared for doping the  $\text{Eu}^{3+}$  ions, followed by x-ray irradiation for 14 h at room temperature. An attempt was made to burn a hole

using a laser with power of  $\sim 300 \text{ mW}$  for 30 min at the wavelength around the peak position of the  ${}^7F_0 \rightarrow {}^5D_0$  transition of the  $\text{Eu}^{3+}$  ions at 298 K, but no hole was observed. Thus, we should point out that the formation of the room temperature PSHB is strongly affected by the glass composition doped with  $\text{Eu}^{3+}$  ions.

### D. Room-temperature hole burning for $\text{Eu}^{3+}$ coupling with $\text{Al}^{3+}$ in glass

In the sol-gel-derived  $\text{Eu}^{3+}$ -doped glasses, we already reported that the spectral hole is burned by the optically activated rearrangement of the OH bonds surrounding the  $\text{Eu}^{3+}$  ions and the hole-depth linearly increases with the increasing OH content.<sup>15,16</sup> Based on these results, the sol-gel technique is a successful method for preparing PSHB glasses with a high hole burning efficiency. However, the formed holes decrease their depth with increasing temperature and are erased above  $\sim 150 \text{ K}$ . The present glasses contain few OH bonds that affect the hole burning. An important feature of the sol-gel-derived glasses is that the room temperature PSHB becomes observable by heating in  $\text{H}_2$  gas or by x-ray irradiation.

With respect to the room temperature PSHB of the  $\text{Eu}^{3+}$  ions, Fujita *et al.* measured the room temperature PSHB of the  $\text{Eu}^{3+}$  ions-doped  $\text{Na}_2\text{O}-\text{Al}_2\text{O}_3-\text{SiO}_2$  glasses melted in hydrogen gas and found that the hole depth increases as the  $\text{Eu}^{2+}$  ion content increases.<sup>12,13</sup> They considered that the hole is formed by the photoinduced reduction of the  $\text{Eu}^{3+}$  ions and the released holes are captured in the  $\text{Eu}^{2+}$  ions. This indicates that the deep holes should be formed as the content of the  $\text{Eu}^{2+}$  ions acting as the hole-trap increases. However, our results indicate no direct evidence for the existence of such a relationship (see Figs. 3 and 4). Furthermore, we observed the room temperature PSHB in the x-ray-irradiated glasses, where the  $\text{Eu}^{3+}$  ions are not changed in  $\text{Eu}^{2+}$  (see Figs. 5 and 6). We also found that the  $\text{SiO}_2$  glass is not appropriate as the matrix glass for the room-temperature PSHB materials, even though it contains the  $\text{Eu}^{2+}$  ions. These results strongly exclude the possibility of the  $\text{Eu}^{2+}$  ions acting as hole traps. At present, we should point out that the room temperature PSHB is only observed in the sol-gel-derived glasses doped with both  $\text{Eu}^{3+}$  and  $\text{Al}^{3+}$ .

In our glass system, the  $\text{Al}^{3+}$  ions are coordinated with the four and/or six oxygens, forming the network structure together with  $\text{Si}^{4+}$  ions. The excess negative charge of the Al-O polyhedra, partly compensated by the  $\text{Eu}^{3+}$  ions, sometimes causes oxygen vacancies in the glass structure. Recently, Jin *et al.* analyzed the glass structure in the  $\text{Sm}_2\text{O}_3-\text{Al}_2\text{O}_3-\text{SiO}_2$  system using the nuclear magnetic resonant spectroscopy and x-ray radial distribution method.<sup>22</sup> The  $\text{AlO}_4$  tetrahedra adjacent to the  $\text{Sm}^{2+}$  ions change into a large size  $\text{AlO}_6$  octahedra and this structure change leads to an enlargement of the vacancies. These structural features would be similar to the  $\text{Eu}_2\text{O}_3-\text{Al}_2\text{O}_3-\text{SiO}_2$  glasses. The sol-gel process is known to bring about many kinds of defects in a glass during its chemical and thermal treatments, which are investigated using optical spectroscopy in the ultraviolet wavelength region.



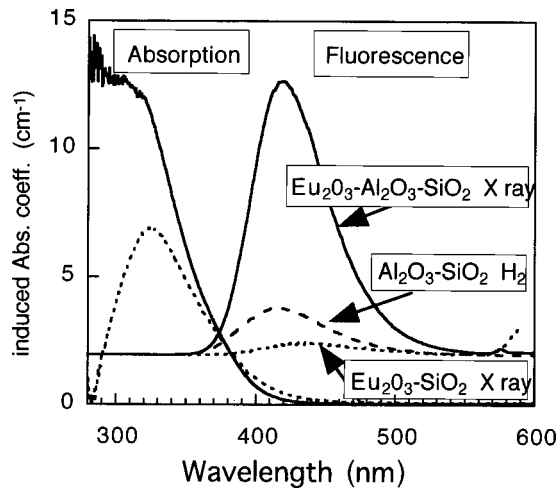


FIG. 8. Difference optical absorption and fluorescence spectra induced in the  $\text{Eu}^{3+}$ -doped  $1\text{Al}_2\text{O}_3 \cdot 9\text{SiO}_2$  (solid lines) and  $\text{SiO}_2$  (dotted lines) glasses irradiated with x ray for 14 h. The fluorescence spectrum for the no  $\text{Eu}_2\text{O}_3$ -containing  $1\text{Al}_2\text{O}_3 \cdot 9\text{SiO}_2$  glass heated in  $\text{H}_2$  gas is also shown (broken line). Fluorescence spectra were measured by exciting using  $\text{N}_2$  laser at 337 nm.

The difference in the optical absorption and fluorescence spectra induced by irradiating the x ray are shown in Fig. 8. In the absorption spectra, the  $\text{Eu}_2\text{O}_3\text{-Al}_2\text{O}_3\text{-SiO}_2$  glass shows a broad absorption band peaking at around 300 nm or below and a shoulder around 320 nm wavelength, while the  $\text{Eu}_2\text{O}_3\text{-SiO}_2$  glass has a relatively sharp band at 320 nm. It is evident that this absorption band should not be assigned to the  $\text{Eu}^{2+}$  ions, because there is no fluorescence from the  $\text{Eu}^{2+}$  ions at 440 nm (see Figs. 2 and 5). Mackey *et al.* measured the optical absorption spectra of the  $\text{Eu}^{3+}$ -doped silicate glasses irradiated with x ray and attributed the induced band at  $\sim 330$  nm to the electron-trapped  $\text{Eu}^{3+}$  ions.<sup>23</sup> This center, designated as an  $[\text{Eu}^{3+}]^-$  state, is considered to be different from the  $\text{Eu}^{2+}$  ions. According to their results, the induced absorption band at around 320 nm in the x-ray-irradiated glass can be attributed to the activated state of the  $\text{Eu}^{3+}$  ions. On the other hand, the induced band at  $\sim 300$  nm or below may be attributed to the defect centers in the glass structure. The most remarkable change in the glass structure is observed in the fluorescence spectra; the  $\text{Eu}_2\text{O}_3\text{-Al}_2\text{O}_3\text{-SiO}_2$  glass has an intense fluorescence band at 420 nm, but the  $\text{Eu}_2\text{O}_3\text{-SiO}_2$  glass has no fluorescence. Previously, we reported the formation of defect centers in the  $\text{Al}_2\text{O}_3\text{-SiO}_2$  glasses. When heated in  $\text{H}_2$  gas, the  $\text{Al}_2\text{O}_3\text{-SiO}_2$  glass containing no  $\text{Eu}_2\text{O}_3$  shows an absorption band at around 220 nm, which is attributed to structure imperfections such as oxygen-deficiency defects in the Al-O polyhedra.<sup>17</sup> This  $\text{Al}_2\text{O}_3\text{-SiO}_2$  glass shows the fluorescence band at 420 nm by x-ray irradiation (see Fig. 8). The optical emission from the glasses heated in  $\text{H}_2$  gas has been extensively investigated for the  $\text{GeO}_2\text{-SiO}_2$  or  $\text{SiO}_2$  glasses for use as optical fibers.<sup>24,25</sup> These glasses have a strong fluorescence around 400 nm, which is attributed to the structure imperfections such as oxygen deficiency, electron, and hole-trap centers. By comparing these glasses, the fluorescence band at 420 nm in the present  $\text{Al}_2\text{O}_3\text{-SiO}_2$  and  $\text{Eu}_2\text{O}_3\text{-Al}_2\text{O}_3\text{-SiO}_2$

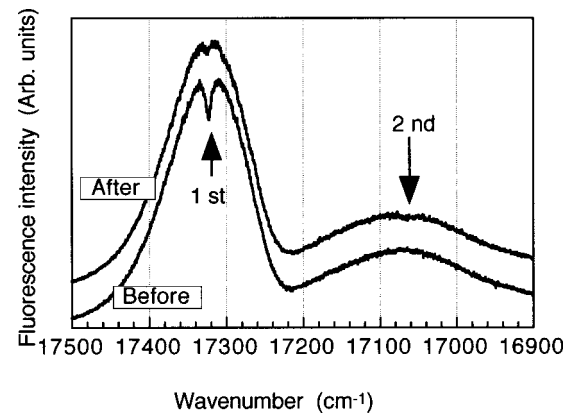


FIG. 9. PSHB spectra, measured at 77 K, burned firstly at  $17\,323\text{ cm}^{-1}$ , followed by irradiating laser with  $17\,065\text{ cm}^{-1}$ . The hole was filled by irradiating the laser with different energy.

glasses can be attributed to the oxygen-deficiency defects such as Al-Al bonds or hole-trapping centers. The formation of these defect centers is enhanced by codoping the  $\text{Eu}^{3+}$ . The oxygen deficiency centers are photosensitive. From these results and the hole burning experiments, the formation of a hole can be considered as follows: A narrow burning laser-beam selectively excites electrons from the ground state of the  $\text{Eu}^{3+}$  ions, and, at same time, the laser resonant with the oxygen-defect centers in the Al-O bonds. This double coupling would make the electron transfer between the excited- $\text{Eu}^{3+}$  ion and defect centers easy, resulting in the formation of a hole. The proposed mechanism of hole burning was examined using a hole-bleaching experiment. The glass in which the hole was first burned on the  ${}^7F_0 \rightarrow {}^5D_0$  transition of the  $\text{Eu}^{3+}$  ions, was irradiated by the laser at a wavelength different from the burning one. A typical result is shown in Fig. 9, where the glass is irradiated at a  $17\,065\text{ cm}^{-1}$  wave number after the first burning at  $17\,323\text{ cm}^{-1}$ . It is evident that the hole burned first is filled upon light irradiation. The finding that the burned holes are stable to temperature and easily erased by a laser with a different energy from that for burning is significant for practical applications as a memory device.

#### IV. CONCLUSIONS

In this paper, we demonstrated that room-temperature persistent spectral hole burning was observed in  $\text{Eu}^{3+}$ -doped  $\text{Al}_2\text{O}_3\text{-SiO}_2$  glasses by heating in  $\text{H}_2$  gas or irradiating the x ray. The treatment of a glass under these conditions brings about many oxygen deficient centers in the glass structure and some  $\text{Eu}^{3+}$  ions were reduced to  $\text{Eu}^{2+}$  in the glass heated in  $\text{H}_2$  gas. The maximum depth of the hole burned at room temperature was found to be  $\sim 10\%$  for both the glasses and independent of the glass treatment conditions. The burnt holes were easily erased by irradiating the laser with an energy different from the burning one. The hole formation could be explained by a model of the excitation of the  $\text{Eu}^{3+}$  ion and subsequent hole trapping in the oxygen-defect centers in the Al-O bonds.

- \* Author to whom correspondence should be addressed. FAX: +81 52 735 5285. Electronic address: nogami@mse.nitech.ac.jp
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